AMENDMENTS TO THE CLAIMS

1. (Previously Presented) A positive working heat-sensitive lithographic printing plate precursor comprising a support having a hydrophilic surface and a coating provided on the hydrophilic surface, said coating comprising:

(a) an infrared light absorbing agent,

(b) an oleophilic resin soluble in an aqueous alkaline developer,

(c) a developer resistance means; and

(d) spacer particles,

wherein said spacer particles comprise aluminum hydroxide or aluminum oxide and have an average particle size larger than 0.4 μm.

2. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said particle size is between 0.5 μm and 20 μm.

3. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said particle size is between 1 μm and 7 μm.

4. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said coating has a layer thickness comprised between 0.6 g/m^2 and 2.8 g/m^2.

5. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said coating comprises at least two layers and wherein said spacer particles are present in at least one of the layers of the coating.

6. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein the amount of said particles in the coating is between 5 and 200 mg/m^2.

7. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said developer resistance means is a polymer comprising siloxane or perfluoroalkyl units.

8. (Original) A stack comprising a plurality of positive working heat-sensitive lithographic printing plate precursors, according to claim 1, wherein adjacent plate precursors are separated by an interleave.

9. (Original) A package comprising a stack according to claim 8.

Claim 10 (Canceled)

11. (Previously Presented) A process for improving the scuff-mark resistance of a positive working heat-sensitive lithographic printing plate precursor comprising providing a support having a hydrophilic surface and applying onto the hydrophilic surface of the support a coating comprising:

(a) an infrared light absorbing agent,

(b) an oleophilic resin soluble in an aqueous alkaline developer,

(c) a developer resistance means; and

(d) spacer particles,

wherein said spacer particles comprise aluminum hydroxide or aluminum oxide and have an average particle size larger than 0.4 μm.

12. (Previously Presented) A positive working heat-sensitive lithographic printing plate precursor according to claim 2, wherein said coating has a layer thickness comprised between 0.6 g/m^2 and 2.8 g/m^2.

13. (Previously Presented) A positive working heat-sensitive lithographic printing plate precursor according to claim 12, wherein said coating comprises at least two layers and wherein said spacer particles are present in at least one of the layers of the coating.

14. (Previously Presented) A positive working heat-sensitive lithographic printing plate precursor according to claim 13, wherein the amount of said particles in the coating is between 5 and 200 mg/m^2.

15. (Previously Presented) A positive working heat-sensitive lithographic printing plate precursor according to claim 14, wherein said developer resistance means is a polymer comprising siloxane or perfluoroalkyl units.

16. (Previously Presented) A positive working heat-sensitive lithographic printing plate precursor according to claim 3, wherein said coating has a layer thickness comprised between 0.6 g/m^2 and 2.8 g/m^2.

17. (Previously Presented) A positive working heat-sensitive lithographic printing plate precursor according to claim 16, wherein said coating comprises at least two layers and wherein said spacer particles are present in at least one of the layers of the coating.

18. (Previously Presented) A positive working heat-sensitive lithographic printing plate precursor according to claim 17, wherein the amount of said particles in the coating is between 5 and 200 mg/m^2.

19. (Previously Presented) A positive working heat-sensitive lithographic printing plate precursor according to claim 18, wherein said developer resistance means is a polymer comprising siloxane or perfluoroalkyl units.

20. (Previously Presented) A positive working heat-sensitive lithographic printing plate precursor according to claim 5, wherein the amount of said particles in the coating is between 5 and 200 mg/m^2.

21. (Previously Presented) A positive working heat-sensitive lithographic printing plate precursor according to claim 20, wherein said developer resistance means is a polymer comprising siloxane or perfluoroalkyl units.

22. (New) A positive working heat-sensitive lithographic printing plate precursor according to claim 1, wherein said coating has a surface, and wherein a plurality of said spacer particles extend above said coating surface.

23. (New) A process according to claim 11, wherein said coating has a surface, and wherein a plurality of said spacer particles extend above said coating surface.

This listing of claims replaces all prior versions, and listings, of claims in the application.